# G-Plate<sup>®</sup>



**Atotech** 

### NEW HMV tool for next generation

### package substrates





#### Particle control

## Best-in-class surface distribution

#### Touch-free PTH equipment for L/S < $5/5 \mu m$

High yield manufacturing is essential for the production of ultra fine-line IC substrates. G-Plate<sup>®</sup> is the next generation solution to overcome all major challenges that limit yield rates. A key feature is the patented equalized curtain flow system to achieve a homogeneous high solution flow along the panel surface. In conjunction with MKS' Atotech's dedicated Printoganth<sup>®</sup> GP series, the system enables ultra thin electroless copper deposits with best-in-class surface distribution and an excellent throwing power into blind micro vias and their wedges.

#### **Features and benefits**

- High yield manufacturing of ultra fine-lines of  $5/5 \,\mu m$ and below
- Touch-free transportation
  - Single panel processing
- Particle control
  - 100% filtration of the solution delivered to panel
  - Clean room conditions for panel chamber
  - Vacuum dryer instead of blower system
- Equalized curtain flow
  - Best-in-class surface distribution
  - Superior solution exchange into BMVs
  - Excellent throwing power
  - Minimized nano void occurrence
- HVM tool, 120 panels/h
  - Automated process control

